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- 1. A carrier head for a chemical mechanical polishing apparatus, comprising:
 - a substrate mounting surface; and
- a retaining ring to maintain a substrate beneath the
- mounting surface during polishing, the retaining ring including a lower portion having a bottom surface for contacting a polishing rad during polishing and an upper portion secured to the lower portion, wherein the lower portion is made of a plastic having a durometer measurement between about 80 and 95 on the Shore D scale and the upper lower portion is made of a metal which is more rigid than the plastic.
- The carrier head of claim 1, wherein the plastic
 is substantially inert to a chemical mechanical polishing process.
 - 3. The carrier head of claim 1, wherein the lower portion is thicker than a substrate to be polished.
 - 4. The carrier head of claim 3, wherein the lower portion is between about 100 and 400 mils thick.
- 5. The carrier head of claim 1, wherein the upper and lower portions are substantially annular in shape.
- 6. The carrier head of claim 1, wherein the plastic is selected from the group consisting of polyphenylene

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sulfide, polyethylene terephthalate, polyetheretherketone, and polybutylene terephthalate.

- 7. The carrier head of claim 6, wherein the plastic is polyphenylene sulfide.
 - 8. The carrier head of claim 1, wherein the metal is selected from the group consisting of steel, aluminum, and molybdenum.

Mof C properto 9. The carrier head of claim 1, wherein the metal material has an elastic modulus about ten to one-hundred times the elastic modulus of the plastic material.

- 10. The carrier head of claim 1, wherein the lower portion is adhesively attached to the upper portion.
- 11. The carrier head of claim 10, wherein the adhesive is a slow curing epoxy.
- 12. The carrier head of claim 1, wherein the lower portion is press fit to the upper portion.
- 13. A retaining ring for a carrier head having a mounting surface for a substrate, comprising:
 - a generally annular lower portion having a bottom

 surface for contacting a polishing pad during polishing, the

 lower portion made of a plastic having a durometer measurement

 between about 80 and 95 on the Shore D scale; and

a generally annular upper portion secured to the lower portion, wherein and the upper lower portion is made of a metal which is more rigid than the plastic.

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